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(71) Applicant (for all designated States except US): **CANON KABUSHIKI KAISHA** [JP/JP]; 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **MIYATA, Hi-rokatsu** [JP/JP]; c/o CANON KABUSHIKI KAISHA,

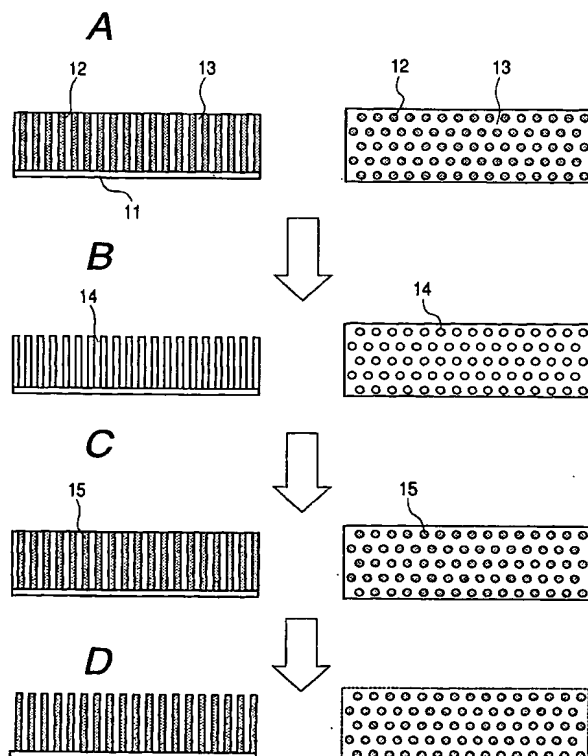
3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **OTTO, Albrecht** [DE/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **KURIYAMA, Akira** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **OGAWA, Miki** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **OKURA, Hiroshi** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **FUKUTANI, Kazuhiko** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP). **DEN, Tohru** [JP/JP]; c/o CANON KABUSHIKI KAISHA, 3-30-2, Shimomaruko, Ohta-ku, Tokyo 146-8501 (JP).

(74) Agents: **OKABE, Masao** et al.; No. 602, Fuji Bldg., 2-3, Marunouchi 3-chome, Chiyoda-ku, Tokyo 100-0005 (JP).

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(54) Title: COLUMNAR STRUCTURED MATERIAL, ELECTRODE HAVING COLUMNAR STRUCTURED MATERIAL, AND PRODUCTION METHOD THEREFOR



(57) Abstract: To obtain a microcolumnar structured material having a desired material. The columnar structured material includes columnar members 15 obtained by introducing a filler into columnar holes formed in a porous material. The porous material has the columnar holes 14 formed by removing columnar substances from a structured material in which the columnar substances 12 containing a first component are dispersed in a matrix member 13 containing a second component capable of forming a eutectic with the first component. The matrix member 13 may be removed. In the columnar structured material, the filler is a conductive material, and an electrode can be structured by electrically connecting the conductive materials in at least a part of a plurality of holes to a conductor.

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